

## **Manufacturability of Electronic Chips<sup>1</sup>**

Rakesh R. Vallishayee and Steven A. Orszag  
Princeton University, Princeton, NJ 08544, USA

Eric Jackson  
Cambridge Hydrodynamics Inc., P.O.Box 1403  
Princeton, NJ 08542, USA

Eytan Barouch  
Boston University, Boston, MA 02144, USA

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### **ABSTRACT**

If the size of features on a microchip are of order of or smaller than the wavelength of the light used in their manufacture, manufacturability of the chip suffers due to diffraction. The degrading effect of diffraction can be handled by biasing masks used for patterning the chips and optimizing stepper parameters are designed and implemented. The algorithms are efficient and feasible for industrial size masks.

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